

5456	((dielectric or SiO or SiO ₂ or (silicon adj oxide) or (silicon adj dioxide)) with (hydrofluoric or HF or (hydrogen adj fluoride)))	USPAT	2004/01/30 13:59	
1508	((dielectric or SiO or SiO ₂ or (silicon adj oxide) or (silicon adj dioxide)) with (hydrofluoric or HF or (hydrogen adj fluoride))) same (photoresist or photoinsensitive or resist)	USPAT	2004/01/30 14:00	
1486	((dielectric or SiO or SiO ₂ or (silicon adj oxide) or (silicon adj dioxide)) with (hydrofluoric or HF or (hydrogen adj fluoride))) same (photoresist or photoinsensitive or resist) and (etch or etching or etchant)	USPAT	2004/01/30 14:00	
283	((dielectric or SiO or SiO ₂ or (silicon adj oxide) or (silicon adj dioxide)) with (hydrofluoric or HF or (hydrogen adj fluoride))) same (photoresist or photoinsensitive or resist) and (etch or etching or etchant) and (organic adj acid) or acetic or citric or formic or ascorbic gluconic malic malonic oxalic succinic or tartaric citric gallic)	USPAT	2004/01/30 14:08	
275	((dielectric or SiO or SiO ₂ or (silicon adj oxide) or (silicon adj dioxide)) with (hydrofluoric or HF or (hydrogen adj fluoride))) same (photoresist or photoinsensitive or resist) and (etch or etching or etchant) and (organic adj acid) or acetic or citric or formic or ascorbic gluconic malic malonic oxalic succinic or tartaric citric gallic) and \$myc<2000	USPAT	2004/01/30 14:06	
74	((dielectric or SiO or SiO ₂ or (silicon adj oxide) or (silicon adj dioxide)) with (hydrofluoric or HF or (hydrogen adj fluoride))) same (photoresist or photoinsensitive or resist) and (etch or etching or etchant) and (HF or hydrofluoric or (hydrogen adj fluoride)) with (organic adj acid) or acetic or citric or formic or ascorbic gluconic malic malonic oxalic succinic or tartaric citric gallic)	USPAT	2004/01/30 14:56	
295	((HF or hydrofluoric or (hydrogen adj fluoride)) with (organic adj acid) or acetic or citric or formic or ascorbic gluconic malic malonic oxalic succinic or tartaric citric gallic)	EPO; JPO	2004/01/30 14:57	
115	((HF or hydrofluoric or (hydrogen adj fluoride)) with (organic adj acid) or acetic or citric or formic or ascorbic gluconic malic malonic oxalic succinic or tartaric citric gallic)) and (etch or etching or etchant)	EPO; JPO	2004/01/30 14:58	
1	4506591.pn.	USPAT	2004/02/02 10:16	

	382	((((citric or acetic or organic) same (hydrofluoric or HF)) and pH) and (etch or etching)) and (dielectric or (silicon adj oxide) or SiO or (silicon adj dioxide) or nitride or SiO ₂ sub.2)	USPAT	2003/12/23 10:37
	221	((((citric or acetic or organic) same (hydrofluoric or HF)) and pH) and (etch or etching)) and (dielectric or (silicon adj oxide) or SiO or (silicon adj dioxide) or nitride or SiO ₂ sub.2)) and (resist or photo\$resist or photo\$insensitive)	USPAT	2003/12/23 10:37
	184	((((citric or acetic or organic) same (hydrofluoric or HF)) and pH) and (etch or etching)) and (dielectric or (silicon adj oxide) or SiO or (silicon adj dioxide) or nitride or SiO ₂ sub.2)) and (resist or photo\$resist or photo\$insensitive) and (selective or selectivity or ratio)	USPAT	2003/12/23 10:39
	156	((((((citric or acetic or organic) same (hydrofluoric or HF)) and pH) and (etch or etching)) and (dielectric or (silicon adj oxide) or SiO or (silicon adj dioxide) or nitride or SiO ₂ sub.2)) and (resist or photo\$resist or photo\$insensitive)) and (selective or selectivity or ratio)) and \$ayc<2000	USPAT	2003/12/23 13:37
	156	((((((citric or acetic or organic) same (hydrofluoric or HF)) and pH) and (etch or etching)) and (dielectric or (silicon adj oxide) or SiO or (silicon adj dioxide) or nitride or SiO ₂ sub.2)) and (resist or photo\$resist or photo\$insensitive)) and (selective or selectivity or ratio)) and \$ayc<2000	USPAT	2003/12/23 13:38
	11	("431485" "5340437" "5389194" "5478436" "5496485" "5800725" "5817185" "5855811" "5972862" "6012469" "6192895").PN.	USPAT	2003/12/23 14:31
	5668	(organic or citric or acetic or asorbic) with (hydrofluoric or HF)	USPAT	2004/01/19 10:47
	253	(organic or citric or acetic or asorbic) with (hydrofluoric or HF); same (resist or photo\$resist or photo\$insensitive)	USPAT	2004/01/19 10:47
	234	((organic or citric or acetic or asorbic) with (hydrofluoric or HF)) same (resist or photo\$resist or photo\$insensitive) and \$ayc<2000	USPAT	2004/01/19 10:36
	3	("5792274" "5962385" "6030932").PN.	USPAT	2004/01/19 10:35
	32	((organic or citric or acetic or asorbic) with (hydrofluoric or HF)) same (resist or photo\$resist or photo\$insensitive) and \$ayc<2000) and pH	USPAT	2004/01/19 10:36
	7	("5783495" "5962385" "5981401" "6103634" "6200905" "6044851" "6319835").PN.	USPAT	2004/01/19 10:36
	6	("3813762" "4087367" "4517106" "4582624" "4761244" "5277835").PN.	USPAT	2004/01/19 10:45
	113	(organic or citric or acetic or asorbic) with (hydrofluoric or HF)	EPO	2004/01/19 10:48
	1	4508591.PN.	USPAT	2004/01/30 13:11
	1540	photo\$resist with (hydro\$ifluoric or HF or (hydrogen adj fluoride))	USPAT	2004/01/30 14:57
	72	(photo\$resist with (hydro\$ifluoric or HF or (hydrogen adj fluoride))) and pH	USPAT	2004/01/30 13:55
	3622	(dielectric or SiO or SiO ₂ sub.2) with (hydro\$ifluoric or HF or (hydrogen adj fluoride))	USPAT	2004/01/30 13:58

Number	Hits	Search Text	DB	Time stamp
16	42	Yates-Donald-L.in.	USPAT; US-PCPUB; EPO; JPO; DERWENT; IBM TDB	2004/02/02 15:26
-	91	photo\$resist and citric and dielectric and (hydrofluoric or HF)	USPAT	2004/01/30 13:53
-	1199	citric same (hydrofluoric or HF)	USPAT	2004/01/19 09:56
-	36	{citric same (hydrofluoric or HF)} and photo\$resist	USPAT	2002/10/15 14:58
-	0	photo\$resist and citric and dielectric and (hydrofluoric or HF)	EPO; JPO; DERWENT; IBM TDB	2002/10/15 15:20
-	1	photo\$resist and citric and (hydrofluoric or HF)	EPO; JPO; DERWENT; IBM TDB	2002/10/15 15:20
-	72	{citric same (hydrofluoric or HF)} and dielectric	USPAT	2002/10/15 15:59
-	56	((citric same (hydrofluoric or HF)) and dielectric) not ((citric same (hydrofluoric or HF)) and photo\$resist)	USPAT	2002/10/15 16:17
-	580	photo\$resist same {citric or acetic or ascorbic}	USPAT	2002/10/15 17:18
-	259	{photo\$resist same {citric or acetic or ascorbic}} and (hydrofluoric or fluoride)	USPAT	2002/10/15 16:18
-	247	((photo\$resist same {citric or acetic or ascorbic}) and (hydrofluoric or fluoride)) not {photo\$resist and citric and dielectric and (hydrofluoric or HF)}	USPAT	2002/10/15 16:18
-	241	((photo\$resist same {citric or acetic or ascorbic}) and (hydrofluoric or fluoride)) not {photo\$resist and citric and dielectric and (hydrofluoric or HF)}) not {citric same (hydrofluoric or HF)}	USPAT	2002/10/15 16:18
-	196	((((photo\$resist same {citric or acetic or ascorbic}) and (hydrofluoric or fluoride)) not {photo\$resist and citric and dielectric and (hydrofluoric or HF)}) not {citric same (hydrofluoric or HF)}) and {dielectric or (silicon adj oxide) or (silicon adj nitride)})	USPAT	2002/10/15 16:19
-	194	((((photo\$resist same {citric or acetic or ascorbic}) and (hydrofluoric or fluoride)) not {photo\$resist and citric and dielectric and (hydrofluoric or HF)}) not {citric same (hydrofluoric or HF)}) and {dielectric or (silicon adj oxide) or (silicon adj nitride)}) and \$ay<2000	USPAT	2002/10/15 16:19
-	5232	{citric or acetic or ascorbic} with {fluoride or HF or hydrofluoric}	USPAT	2002/10/15 17:19
-	275	((citric or acetic or ascorbic) with {fluoride or HF or hydrofluoric}) same {silicon adj oxide} or {silicon adj dioxide} or dielectric)	USPAT	2002/10/15 17:20
-	228	((citric or acetic or ascorbic) with {fluoride or HF or hydrofluoric}) same {silicon adj oxide} or {silicon adj dioxide} or dielectric) not (((photo\$resist same {citric or acetic or ascorbic}) and {hydrofluoric or fluoride}) not {photo\$resist and citric and dielectric and (hydrofluoric or HF)}) not {citric same (hydrofluoric or HF)}) and {dielectric or {silicon adj oxide} or {silicon adj nitride})	USPAT	2002/10/15 17:20